

<b>Notice of References Cited</b>	Application/Control No. 10/594,152	Applicant(s)/Patent Under Reexamination KOINUMA ET AL.	
	Examiner ANTHONY HO	Art Unit 2815	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
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**FOREIGN PATENT DOCUMENTS**

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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Haemori et al, "Fabrication of Highly Oriented Rubrene Thin Films by the Use of Atomically Finished Substrate and Pentacene Buffer Layer," Japanese Journal of Applied Physics, Vol. 44, NO. 6A, 2005, pp. 3740-3742
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